

Running Projects

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1st DRD3 Workshop Working group 3 (WG3) Session 19th June 2024



RD50-2023-05: PAB - Partial Activation of Boron to enhance DRD3 the radiation tolerance of the gain implant

- **Title:** "Partial Activation of Boron to enhance the radiation tolerance of the gain implant PAB"
- Project Leader: Valentina Sola (Torino University)
- Participating institutes: 12 (all RD50 members)
- Indicated project cost: 52 keuros
- Request to RD50: 27 keuros
- Granted RD50 contribution: 27 keuros

RD50 funding request - Date: 15.11.2023 -

- Title of project: Partial Activation of Boron to enhance the radiation tolerance of the gain implant PAB
- Contact person: V. Sola Torino University and INFN +39 011 670 7338 valentina.sola@to.infn.it

RD50 Institutes:

- 1. INFN Torino, V. Sola valentina.sola@to.infn.it
- 2. Centro Nacional de Microelectrónica, G. Pellegrini giulio.pellegrini@imb-cnm.csic.es
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- 4. Jožef Stefan Institute, G. Kramberger Gregor.Kramberger@ijs.si
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- 7. CERN, M. Moll michael.moll@cern.ch
- 8. University of Montenegro, G. Medin gordana.medin@gmail.com
- 9. National Institute of Materials Physics (Romania), I. Pintilie ioana@infim.ro
- 10. Institut für Hochenergiephysik, T. Bergauer Thomas.Bergauer@oeaw.ac.at
- 11. Vilnius University, T. Čeponis tomas.ceponis@ff.vu.lt
- 12. Instituto de Física de Cantabria (CSIC), I. Vila Álvarez ivan.vila@csic.es

Request to RD50: € 27,000 Total project cost: € 52,000

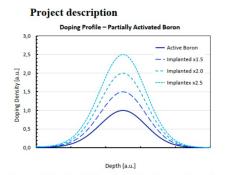


Figure 1: Profile of dopant density forming the gain implant of LGAD sensors exploiting partial activation of boron. Different doses of implanted boron are shown. The goal is to keep a constant dose of active dopant, indicated as dose 1, while studying the effect of different implant concentrations.



HIGH TEMP

FRACTION OF FREE CARRIERS VS ANNEALIN TEMPERATURE

T. . 25*C

- • 30 mi

150 keV BORON

\$ = 2.5 ×10

EGION I REGIONIE REGIONIE

500 600 700 800

T, (*C)

Figure 2: Isochronal annealing of boron. The fraction of activated boron, p/ϕ , is plotted against the

annealing temperature, TA, for different implant

doses, 6. The annealing time is 30 minutes[3].

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RD50-2023-06: Impact ionization parameterization at

DRD3

DRD3

- Title: "Impact ionization parameterization at extreme fluences"
- Project Leader: Gregor Kramberger (Ljubljana)
- Participating institutes: 5 (all RD50 members)
- Indicated project cost: 52 keuros
- Request to RD50: 25 keuros

extreme fluences

Granted RD50 contribution: 25 keuros

RD50 fundin	g request
- November,	2023 -

Title of project:

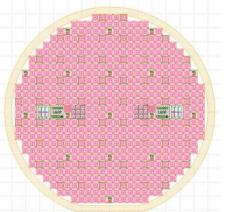
Impact ionization parametrization at extreme fluences **Contact person:** Gregor Kramberger Jožef Stefan Institute +386 1 477 3159 Gregor.Kramberger@ijs.si

RD50 Institutes:

- 1. CNM, Giulio Pellegrini, giulio.pellegrini@imb-cnm.csic.es
- 2. JSI Ljubljana, Gregor Kramberger, <Gregor.Kramberger@ijs.si>
- 3. INFN-Torino, Valentina Sola </ doi:10.1016/january.com/sola@cern.ch>
- 4. UCG, Gordana Medin <gordana.medin@gmail.com>
- 5. CERN, Michael Moll < Michael.Moll@cern.ch>

Request to RD50: 25000 € Total project cost: 52000 €

We propose processing of several wafers of small size pin and LGAD samples (see Fig. 1) where the doping of the gain layer would be significantly higher than in presently produced LGADs (1e16-1e17 cm⁻³) so that the produced LGADs would not be operational before irradiation, but would be become operational after irradiations when sufficiently large number of initial acceptors were removed to allow depletion of gain layer, establishing electric field in the bulk and not leading to the immediate break-down of the devices. That



• 1, 2, 10, 100 a.u. (B+C LGADs) • 1, 5, 20, 200 a.u. (B LGADs) • 1 a.u. (C-implanted PINs)

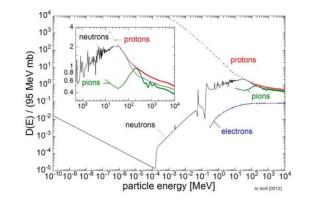
Figure 1: View of the wafer layout (6").



RD50-2023-07

RD50-2023-07: PIN sensors for dosimetry & NIEL studies DRD3

- · Title: "PIN sensors for dosimetry and NIEL studies"
- Project Leader: Michael Moll (CERN)
- Participating institutes: 4 (all RD50 members)
- Indicated project cost: 40 keuros
- Request to RD50: 20 keuros
- Granted RD50 contribution: 20 keuros



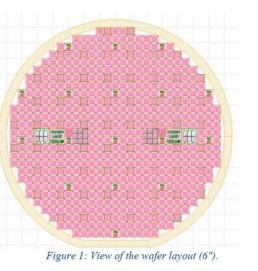
Project description:

The objective of this project is to produce n-in-p diodes in form of simple "pin sensors" that can be used as passive radiation monitoring devices by measuring the radiation induced leakage current in well-defined post-irradiation annealing and operational conditions.

The purpose of the project is two-fold:

[1] Dosimetry: The sensors will serve as dosimetric devices for radiation monitoring in irradiation campaigns at the JSI nuclear reactor and the CERN IRRAD facility in the context of RD50/DRD3 collaboration projects.

[2] Facility Intercomparison/NIEL study; The sensors will serve a measurement campaign for the cross-comparison of irradiation facilities. For the intercomparison of irradiation facilities, a set of sensors will be provided free of charge to interested irradiation facilities within the RD50/DRD3 collaboration for exposure at their facility under well controlled dosimetric conditions. After exposure, the sensors will then either be measured at the facility under well defined conditions (after annealing of 80 minutes at 60C at a specified bias voltage to be determined after processing of the sensors, with guard ring connected) or shipped to CERN were the corresponding measurements will be performed. The ultimate scientific goal is to evaluate the validity of the Non-Ionizing Energy Loss (NIEL) hypothesis by means of measuring the leakage current of the sensors after irradiation. This study is accompanied by simulation studies at CERN using FIUKA, GEANT4 and TRIM simulations to evaluate the expected Non-Ionising Energy Loss (NIEL) against the measured leakage current increase.



RD50 funding request - November, 2023 -

 Title of project:
 PIN sensors for dosimetry and NIEL studies

 Contact person:
 Michael Moll

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- 2. CNM, Giulio Pellegrini, giulio.pellegrini@imb-cnm.csic.es
- 3. JSI Ljubljana, Gregor Kramberger, Gregor.Kramberger@ijs.si
- 4. NIMP Bucharest, Ioana Pintilie ioana@infim.ro

Request to RD50: 20000 € Total project cost: 40000 €

DRD3

	RD50 funding request	RD50-2022-01
Date:		
17.05.2022		the entry law in LCADe
The of the project	Defect engineering in PAD diodes mimicking	g the gain layer in LGADs
RD50 Institutes:	D50 Institutes: - NIMP, Ioana Pintilie, <u>ioana@infim.ro</u>	
	- CERN, Michael Moll, Michael.moll@cerr	<u>n.ch</u>
	- CiS, Kevin Lauer, klauer@cismst.de	
	- JSI, Gregor Kramberger, Gregor.Kramberger@ijs.si	
	- HH, Eckhart Fretwurst, Eckhart.fretwurst@desy.de	
	- INFN-Torino, Valentina Sola, sola.valentina@gmail.com	
	-Vilnius University, Tomas Ceponis, tomas	.ceponis@ff.vu.lt
Request to RD50:	26665 EUR	
Total project costs	51165 EUR	

Project description:

The proposed project is focusing on the acceptor removal process (ARP) in the irradiated gain layer of LGAD sensors, aiming to understand it and parametrize it for various content of B, C and O impurities and irradiation fluences, in order to find proper defect engineering solutions to maximize the radiation hardness of the gain layers. The studies performed so far on LGAds show that in the p⁺ layer of LGADs, the ARP can result in a complete disappearance of the gain at 1MeV neutron equivalent fluences higher than $2x10^{15}$ cm⁻². As major obstacles preventing the achievement of enough knowledge for characterizing and proposing feasible solutions for improving the performance of the gain layers in LGADS are:

Title: "Defect engineering in PAD diodes

Indicated project cost: 51.2 keuros

Granted RD50 contribution: 26.7 keuros

Request to RD50: 26.7 keuros

Ref-FZ-A

(1.5 Ωcm)

Ref-FZ-B

(15 Ωcm)

Ref-FZ-A-P

(1.5 Ωcm+P)

Carbon and Phosphorous compensation

G-FZ-A-C1

G-FZ-B-C1

G-FZ-A-P-C1

G-FZ-A (1.5 Ωcm)

G-FZ-B (15 Ωcm)

 $G-FZ-A-P(1.5\Omega cm+P)$

mimicking the gain layer in LGADs "

Ref-FZ-A

(1.5 Ωcm)

Ref-FZ-8 (15 Ωcm)

Ref-FZ-A-P

G-FZ-A-PC2

... different Boron doped wafer type with/without

(1.5 Ωcm+P)

G-FZ-B-C1

G-FZ-A-C2

Ref-FZ-A

(1.5 Ωcm)

Ref-FZ-B (15 Ocm)

Ref-FZ-A-P

(1.5 Ωcm+P)

G-FZ-A-P-C3

G-FZ-A-C3

G-FZ-B-C1

Project Leader: Ioana Pintilie (NIMP, Bucharest)
Participating institutes: 7 (all RD50 members)